

ABSTRACT

There are provided a developing solution, which can develop a photosensitive composition in a simple manner while
5 maintaining satisfactory sensitivity and resolution, and a method for pattern formation using said developing solution. This developing solution comprises a compound containing a hydrophilic group(s) selected from the group consisting of an amine-N-oxide group, a sulfonate group, a sulfate group, a
10 carboxylate group, and a phosphate group, and is particularly suitable for use in the development of a photosensitive composition comprising a silicon-containing polymer. The present invention also relates to a method for pattern formation using the developing solution.